

#3/Pre  
Amended  
RG  
10-28-98

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Divisional Patent  
Application of

Junichi SATO

Serial No. Not Assigned

Filed: **Herewith**

For: CHEMICAL-MECHANICAL  
POLISHING PROCESS

Group Art Unit: 1763

Examiner: T. Weingart

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents  
Washington, DC 20231

Sir:

Prior to an initial examination on the merits, please  
amend the above-identified continuation application as  
follows:

IN THE SPECIFICATION:

On page 1, line 15, delete "to".

On page 2, line 7, delete "more".

On page 5, line 3, insert -- . -- following "sialon";  
lines 15 to 16, change "the use of silica base slurry has a  
difficulty in more increasing a polishing rate" to -- it is  
difficult to increase the polishing rate when using a silica  
base slurry --.

On page 13, line 14, change "was" to -- were --.

On page 14, line 4, change "in" to -- at --; line 9,

0916150-025160